

NO_x REMOVAL USING DBD WITH UREA SOLUTION AND PLASMA TREATED TiO₂ PHOTO CATALYST

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ABSTRACT

Two kinds of experiments for NO_x removal have been carried out. One is the experiment using dielectric barrier discharge (DBD) with the aid of adding urea solution. The other is the experiment with plasma treated TiO₂ photo catalyst. For adding urea solution the energy efficiency of NO_x removal by DBD is better than without the adding by more than 10 times at Vac ~7.2kV. The adding water only also shows good result. So the improvement in NO_x removal by DBD with urea solution is not only due to urea but also water. TiO₂ films are developed on the one side of a quartz tube at 500°C by use of the sol-gel method. Then the TiO₂ films have been processed in hydrogen or nitrogen plasma. The difference of NO_x removal rate between the plasma treated films and no treated films has been measured, in which measurements a chemical lamp, black light and fluorescent lamp were used. The results show that the hydrogen plasma treated film is the most efficient as photo catalyst for NO_x removal.

INTRODUCTION

The harmful effects of NO_x(NO and NO₂) such as the formations of photochemical smog and acid rain as well as unfavourable effects on human respiratory system are well known. NO_x is formed in all combustion processes from the high temperature reaction between N₂ and O₂.

Two kinds of experiments for NO_x removal have been carried out. One is the experiment using dielectric barrier discharge (DBD) with the aid of adding urea solution. The other is the experiment with plasma treated TiO₂ photo catalyst.

The selective catalytic reduction(SCR) of NO_x with a reducing agent, i.e. NH₃ is one of the most successful technique for the removal of NO_x in power generation plants.

The NH₃ selectively reacts with NO_x components of an exhaust gas without reacting with O₂ (Bosch and Janssen (1988)). However, it would not be possible to use NH₃ on a diesel powered car because it is corrosive, toxic and difficult to store, transport and handle. It has been proposed that NH₃ could be replaced by aqueous solutions of urea ((NH₂)₂CO) by Held, Konning and Puppe (1990) and much interest has been focused on using urea as a safer source of ammonia in automotive applications (for example Sullivan and Doherty (2005), Li, Jones, Grassian and Larsen (2005)).

On the other hand Takei et al (1998) proposed to reduce NO_x without any catalysts but with urea. But it requires high temperature (800~1000.) and high concentration of NH₃. We think that NO_x could be reduced by dielectric barrier discharge with aqueous solution of urea without any catalysts at room temperature.

TiO₂ is also known to remove NO_x by oxidizing NO to NO₂ and NO₂ being adsorbed by active carbon for example. It was found by Masuo and Kato (1959) that substances on TiO₂ were photo-oxidized. However, TiO₂ can only be activated by UV light (<380nm). It is more useful if TiO₂ can be activated by visible light as well as UV light. Nitrogen-doped TiO₂ (TiO_{2-x}N_x)(Morikawa et al (2005)) and declined composition of the O/Ti TiO₂ (TiO₂(surface) to TiO_{1.9}(bottom)) (Kitano et al (2005)) have been proposed as practical visible light-responsive TiO₂. Those TiO₂ thin films were prepared on glass substrates, for example, by sputtering a TiO₂ target in an N₂(40%)/Ar gas (the former) and Ar gas (the latter). In the present work, TiO₂ thin films were prepared by use of the sol-gel method and then the films were reformed by exposed to N₂ or H₂ plasma, which were produced by a surface wave plasma source.

In this paper, first the NO_x removal experiments using DBD with urea solution and then visible light sensitive TiO₂ film will be reported.

EXPERIMENTS AND RESULTS

NO_x Removal by DBD with Urea Solution

Experiment

Fig.1 shows the experimental setup for NO_x removal by DBD with urea solutions. The discharge tube made of pyrex glass (inner diameter: 19.5 mm., outer diameter: 23.0 mm., length: 200 mm.) is wounded by Cu foil, which works as an outer electrode. A screw rod made of brass (2mm.) is set at the centre of the discharge tube as an inner electrode. AC high voltage (50Hz, 7-11 kV_{p-p}) was applied between the two electrodes and then DBD took place inside the tube. The mimic exhaust

gas (N₂ (NO:780ppm included):1000cc/min, O₂:125cc/min) is run into the discharge tube after through a bubbling pot which contains water or an aqueous urea solution or nothing. The concentrations of NO and NO_x after passing through the discharge tube are measured by a NO_x detector (testo350., TESTO). The weight of urea dissolved in water is 10 – 50g/100ml.

Results

The dependence of the NO removal rate on the urea concentration in an aqueous solution is shown in Fig.2. The parameters in Fig. 2 are the weight percentage (= (urea weight)/(urea + water weight)*100). One can see that the most effective concentration for NO removal is about 23%. Figure 3 compares NO removal rates among no adding, water adding and an aqueous urea solution (concentration 23%) adding. This graph indicates that adding an aqueous urea solution is effective for NO removal.

NO_x Removal by TiO₂ Thin Film

Experiment

A TiO₂ thin film was sintered on the one side of a half quartz tube at 500 . by use of the sol-gel method. The detail how to make a TiO₂ film on the tube was found elsewhere (Katamoto et al (2004)). Then the TiO₂ thin film was processed by H₂ or N₂ plasma to be responsible to visible light. After that the half of quartz tube was stucked with another half of a clear quartz tube without any TiO₂ films. A surface wave plasma source is used for processing the TiO₂ film and the setup of the plasma source is shown in Fig.4. The parameters of the plasma source are listed in Table1. The detail of the plasma source (a surface wave plasma source) is described elsewhere (Takahashi (2003)).

Table 1: Parameters of plasma source

Gas spices	H ₂ or N ₂
Gas pressure	1 torr
Microwave power	100 W
Microwave frequency	2.45 GHz
Plasma exposure time	30 min.

The NO removal experimental setup with the TiO₂ photo catalyst is shown in Fig.5. The reactor made of a quartz tube (inner diameter: 19.5 mm., outer diameter: 22.5 mm., length: 120 mm.), a half of which is coated by a TiO₂ film, is irradiated by three kinds of fluorescent lamps. They are an ordinary fluorescent lamp (FL6D, TOSHIBA Co.), a chemical lamp (FL10BL, TOSHIBA Co.) and a black lamp (FLBLB, TOSHIBA Co.). The mimic exhaust gas (N₂ (NO:780ppm included):1000cc/min, O₂:125cc/min) is run into the reactor tube through a bubbling pot which contains water. The concentrations of NO and NO_x after passing through the reactor tube are measured by a NO_x detector (test 350, TESTO).

Results

Table 2 shows the comparison of NO removal rates among an ordinary TiO₂ film, a H₂ plasma processed film and a N₂ plasma processed TiO₂ film. For the ordinary fluorescent lamp no processed TiO₂ film almost can't oxidize NO. The best value is obtained in the case of H₂ plasma processed TiO₂ film with the chemical lamp (FL10BL).

Table 2: Comparison of NO removal rate among different TiO₂ films

	No processed TiO ₂ film	H ₂ plasma processed one	N ₂ plasma processed one
Fluo. lamp	0.08 %	1.05 %	0.93 %
Chemical lamp	0.76 %	1.32 %	1.24 %
Black lamp	0.59 %	0.99 %	0.98 %

SUMMARY

In NO_x removal by DBD it is effective to add urea solution and in the present experiment the most effective concentration of urea in an aqueous solution is 23%.

H₂ or N₂ plasma treated TiO₂ thin films can be activated by an ordinary fluorescent lamp and oxidize NO.

ACKNOWLEDGMENTS

The authors thank Ms. Yokoyama K., Mrs. Kozuka S. and Hirohashi S. for providing TiO₂ thin films.

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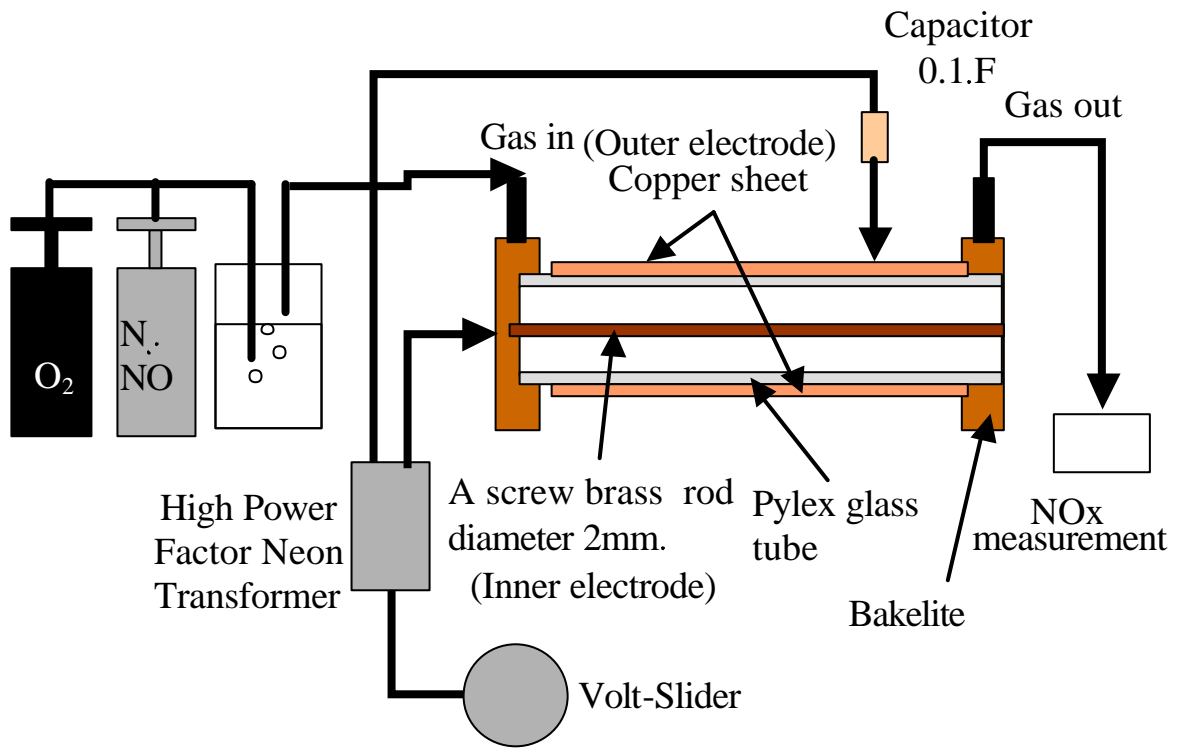


Figure 1: DBD experimental setup

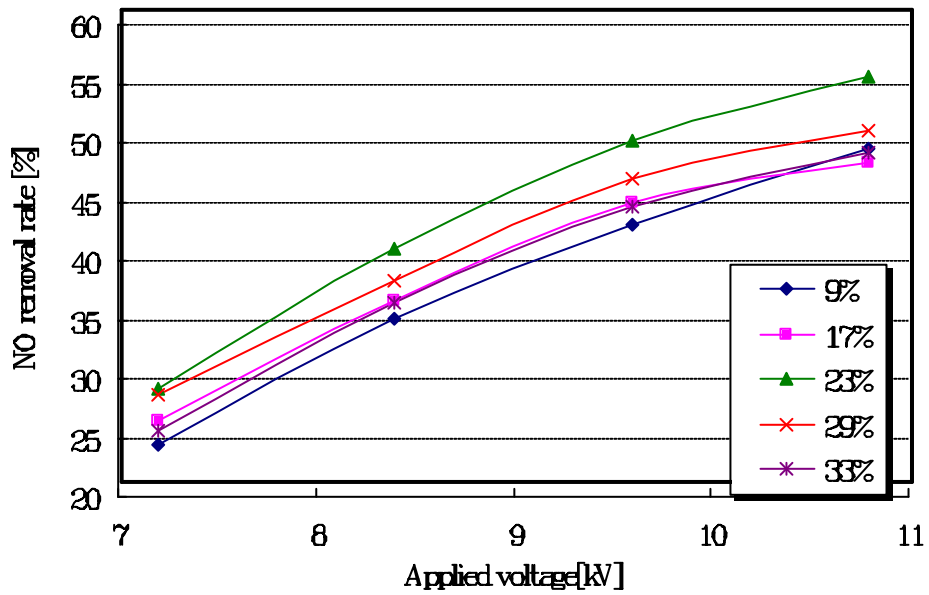


Fig2 The dependence of NO removal rate on urea concentration

Figure 2: Dependence of NO removal rate on urea concentration

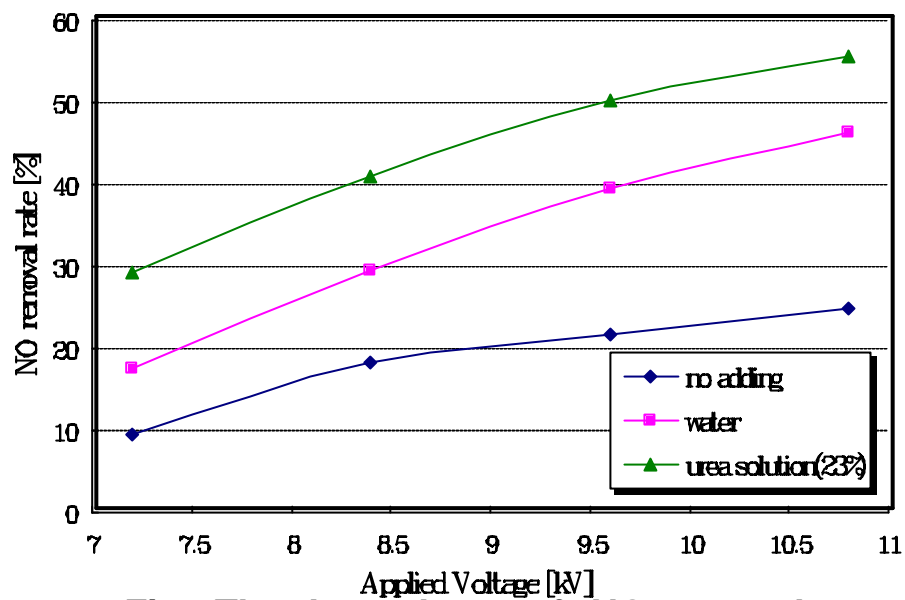


Fig3 The dependence of NO removal rate

Figure 3: Dependence of NO removal rate on applied voltage

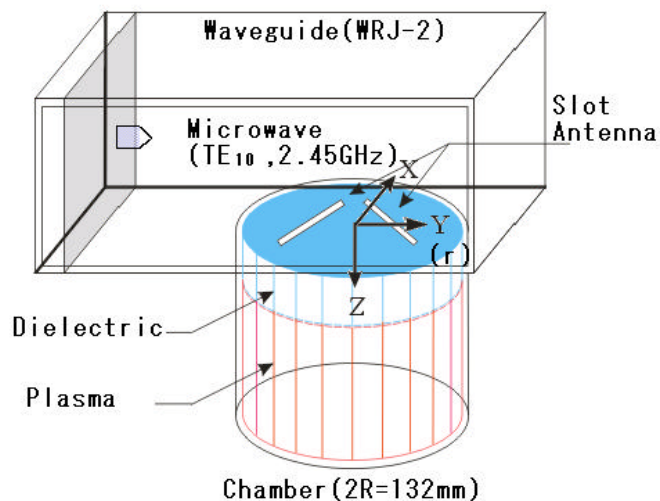


Figure 4: Surface wave plasma source setup

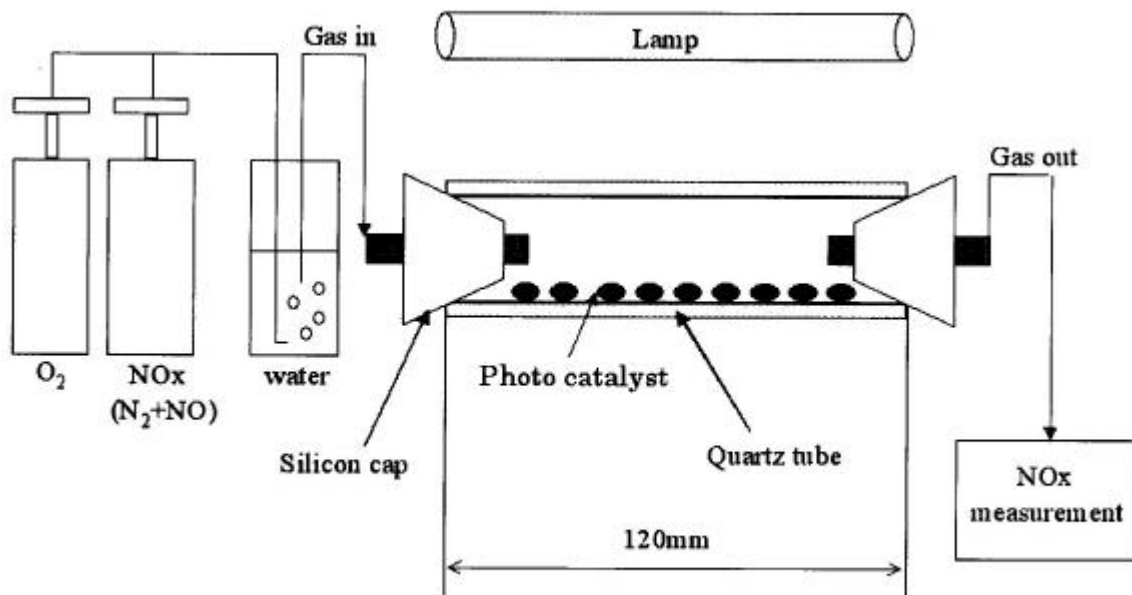


Figure 5: NO removal experimental setup with TiO_2 film